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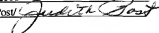
Applicants:	Ogata, et al.	Examiner:	Lee, Sin J.
Application No.:	10/589,382	Group Art Unit:	1795
Confirmation No:	6030	Docket:	1608-6 PCT/US
Filed:	August 15, 2006	Dated:	May 22, 2008
For:	PHOTORESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN		

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Dated: May 22, 2008

Signature: Judith Post 

**SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT**

Sir:

In order to fulfill the requirements of candor and good faith set forth in 37 C.F.R. §1.56, Applicants submit herewith the following Supplemental Information Disclosure Statement in accordance with the provisions of 37 C.F.R. §1.97 and §1.98. The documents are listed on PTO Form 1449. We have enclosed the cited document.

The foreign document listed on the Form-PTO 1449, i.e., JP 2000344764, is not in the English-language. This reference was cited in the corresponding Taiwanese patent application. As the cited foreign document is not in English, Applicants are submitting herewith an English-language abstract in addition to the foreign-language documents.

The Commissioner is hereby authorized to charge payment of any additional fees associated with this communication, or credit any overpayment, to Deposit Account No. 08-2461. Such authorization includes authorization to charge fees for extensions of time, if any, under 37 C.F.R. § 1.17 and also should be treated as a constructive petition for an extension of time in this reply or any future reply pursuant to 37 C.F.R. § 1.136.

If the Examiner has any questions or comments relating to the present application, he or she is respectfully invited to contact Applicants' attorney at the telephone number set forth below.

Respectfully submitted,

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